

Abstract

5 The present invention is directed to a precious metal
sputtering target having a columnar crystallographic
microstructure such that crystals are grown in a direction
normal to the sputtering surface in order to solve
conventional problems. The high-purity sputtering target of
10 the present invention prevents chipping of a minute cluster
mass that occurs in a sputtering target produced through
casting or powder metallurgy; produces thin film of excellent
quality; and has considerably reduced internal defects.

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